

REMARKS

Reconsideration and withdrawal of the rejections set forth in the above-mentioned Office Action in view of the foregoing amendments and the following remarks are respectfully requested.

Claims 1-11 are now pending in this application, with Claim 1 being the sole independent claim. Claims 1-8 have been amended and Claims 10 and 11 are newly-presented herein. Support for certain features of the claims can be found in the specification at least page 16 (Claims 1 and 2), page 20 (Claim 10), and pages 44-46 (Claim 11). Of course, the claims are not intended to be limited in scope to this preferred embodiment.

Claims 1-3 and 7-9 were rejected under 35 U.S.C. § 103 as being obvious over European Patent Application No. 1 380 422 (Kubota et al.) in view of Japanese Laid-Open Patent Application No. 9-183928 (Kazuhiko et al.). Claims 4-6 were rejected under 35 U.S.C. § 103 as being obvious over Kubota et al. in view of Kazuhiko et al. and in further view of U.S. Patent Application Publication No. 2003/0215743 (Goto). These rejections are respectfully traversed.

In the present invention, a discharge port can be formed in a coating resin layer formed on a solid layer through a photolithographic process. The coating resin layer contains a cationically polymerizable resin, a cationic photopolymerization initiator and an inhibitor of cationic photopolymerization. With such a method, scum can be controlled when a coating resin layer is exposed and developed for patterning.

Kubota et al. is directed to the formation of a liquid jet recording head in which a substrate 201, on which energy generating elements 202 are arranged, is coated with a crosslinking positive resist layer 203. The material of the crosslinking positive resist layer 203 is a copolymer of methylmethacrylate and methacrylic acid. A PMIPK positive resist layer 204 is coated on the resist layer 203, resist layer 204 is exposed using a deep UV exposure device, and resist layer 204 is developed to form a pattern. Subsequently, resist layer 203 is exposed and developed to form a pattern.

That is, as understood by Applicants, Kubota et al. describes a method for manufacturing a recording head in which a cationically polymerizable resin is patterned through a photolithographic process. However, as recognized in the Office Action, Kubota et al. does not disclose or suggest at least a material used for a coating resin layer that contains a cationically polymerizable resin, a cationic photopolymerization initiator and an inhibitor of cationic photopolymerization, as is recited in independent Claim 1.

Thus, Kubota et al. fails to disclose or suggest important features of the present invention recited in the independent claim.

As understood by Applicants, Kazuhiko et al. discloses an inhibitor of polymerization, without disclosing any details of the inhibitor. However, Applicants submit that Kazuhiko et al. does not utilize a photolithographic process. Accordingly, one of ordinary skill in the art would not look to the teachings of Kazuhiko et al. to modify the method of Kubota et al.,

which does utilize a photolithographic process. Thus, Kubota et al. and Kazuhiko et al. would not be combined to meet the features of the present invention recited in independent Claim 1.

Goto is directed to an image forming material used in the production of a color filter. A photosensitive resin layer is transferred on a surface of a desired member. The photosensitive resin layer can contain a thermal polymerization inhibitor and several examples of the inhibitor are disclosed. However, Goto is not directed to a method for manufacturing a liquid discharge head and is not believed to remedy the deficiencies of the citations noted above with respect to independent Claim 1.

Thus, Claim 1 is patentable over the citations of record. Reconsideration and withdrawal of the § 103 rejections are respectfully requested.

For the foregoing reasons, Applicants respectfully submit that the present invention is patentably defined by independent Claim 1. Dependent Claims 2-11 are also allowable, in their own right, for defining features of the present invention in addition to those recited in independent Claim 1. Individual consideration of the dependent claims is requested.

Applicants submit that the present application is in condition for allowance. Favorable reconsideration, withdrawal of the rejections set forth in the above-noted Office Action, and an early Notice of Allowability are requested.

Applicants' undersigned attorney may be reached in our Washington, D.C. office by telephone at (202) 530-1010. All correspondence should continue to be directed to our below-listed address.

Respectfully submitted,

/Mark A. Williamson/

Mark A. Williamson
Attorney for Applicants
Registration No. 33,628

FITZPATRICK, CELLA, HARPER & SCINTO
30 Rockefeller Plaza
New York, New York 10112-3801
Facsimile: (212) 218-2200
MAW:ytr

FCHS_WS 2772598v1